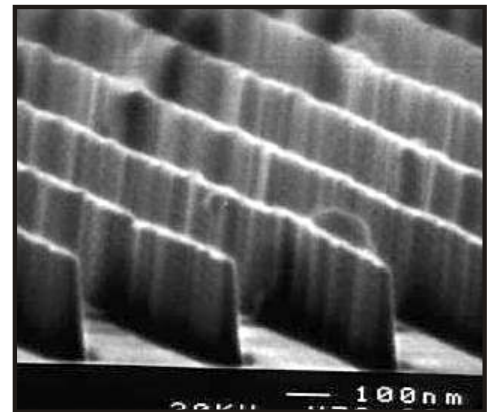
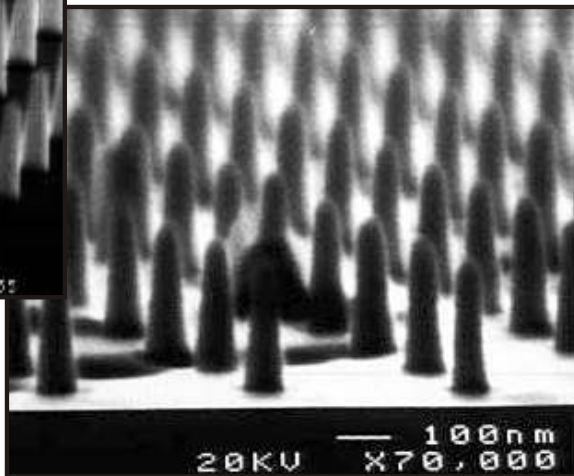
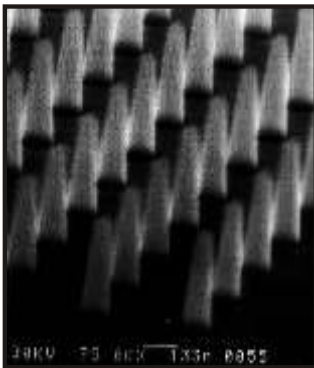


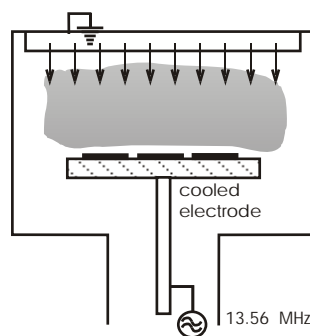
Plasmalab Data

Sub μm anisotropic ZnSe RIE



Courtesy of the Institut für
Halbleiterphysik, University of Linz

Plasmalab 80 Plus



Technology:

- Low Pressure - RIE
- Parallel Plate Reactor
- 13.56 MHz Plasma Excitation
- Shower Head Gas Inlet
- Process Gas: CH_4 , H_2

Results:

- Rate: 16 nm/ min
- Mask used here: Ti
- (Selectivity to Photoresist ca 20 : 1
at up to 25 nm/ min)

Plasmalab System 133

Plasmalab System 100

